

3885-0103P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant:

Yoshinobu ONO et al.

Conf.: 2546

Appl. No.:

10/046,741

Group:

2815

Filed:

January 17, 2002

Examiner: S. Mulp

For:

METHOD FOR FABRICATING III-V COMPOUND

SEMICONDUCTOR

REPLY UNDER 37 C.F.R. § 1.111

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 June 19, 2003

Sir:

In reply to the Office Action dated December 20, 2003, the due date having been extended three (3) months, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE CLAIMS

(New) A method for fabricating a III-V Group compound semiconductor comprising a step of on a flat GaAs substrate by epitaxial growth an $Al_{yj}Ga_{1-yj}As$ multiplayer structure (0 \leq yj < 1, j